

Title (en)
NANOFILM PROTECTIVE AND RELEASE MATRICES

Title (de)
NANOFILMSCHUTZ- UND ABLÖSEMATRIZEN

Title (fr)
MATRICES DE PROTECTION ET DE LIBÉRATION EN NANOFILM

Publication
EP 2257971 A4 20121128 (EN)

Application
EP 08871004 A 20081218

Priority

- US 2008013918 W 20081218
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- US 7298108 P 20080404
- US 15029808 A 20080425
- US 8008208 P 20080711

Abstract (en)
[origin: WO2009091384A1] A modified atomic plasma deposition (APD) procedure is used to produce amorphous, nonconformal thin metal film coatings on a variety of substrates. The films are porous, mesh- like lattices with imperfections such as pinholes and pores, which are useful as scaffolds for cell attachment, controlled release of bioactive agents and protective coatings.

IPC 8 full level
C23C 16/455 (2006.01); **A61F 2/00** (2006.01); **A61L 27/10** (2006.01); **B32B 15/01** (2006.01); **C23C 16/00** (2006.01); **C23C 16/40** (2006.01); **C23C 16/50** (2006.01); **H01L 21/205** (2006.01)

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A61F 2/00 (2013.01); **A61L 27/10** (2013.01); **A61L 27/105** (2013.01); **A61L 27/30** (2013.01); **A61L 27/54** (2013.01); **A61L 27/56** (2013.01); **A61L 31/082** (2013.01); **A61L 31/146** (2013.01); **A61L 31/16** (2013.01); **C23C 16/006** (2013.01); **C23C 16/403** (2013.01); **C23C 16/405** (2013.01); **C23C 16/45536** (2013.01); **A61L 2400/18** (2013.01)

Citation (search report)

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- [X] US 2004121451 A1 20040624 - MORITZ NIKO [FI], et al
- [X] NISKANEN A ET AL: "Low temperature deposition of aluminium oxide by radical enhanced atomic layer deposition", JOURNAL OF THE ELECTROCHEMICAL SOCIETY, vol. 152, no. 7, 10 June 2005 (2005-06-10), The Electrochemical Society, Pennington, NJ [US], pages F90 - F93, XP002518833, ISSN: 0013-4651, [retrieved on 20050610], DOI: 10.1149/1.1931471
- [XII] NISKANEN A ET AL: "Radical enhanced atomic layer deposition of titanium dioxide", CHEMICAL VAPOR DEPOSITION, vol. 13, no. 4, 4 April 2007 (2007-04-04), Wiley-VCH Verlag, Weinheim [DE], pages 152 - 157, XP001507380, ISSN: 0948-1907, DOI: 10.1002/CVDE.200606546
- See references of WO 2009091384A1

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AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MT NL NO PL PT RO SE SI SK TR

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US 2008013918 W 20081218; CN 200880128157 A 20081218; EP 08871004 A 20081218